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(54) Title: MATERIAL HAVING A LOW DIELECTRIC KONSTANT AND METHOD OF MAKING THE SAME

(57) Abstract: There is disclosed a method for producing a highly cross-linked polypropylene material by plasma polymerisation of a carbon containing gas, not specifically propylene, exhibiting low relative permittivity, high thermal stability and enhanced mechanical properties, said method and material being suitable for application not limited to interlayer dielectric deposition in microchip fabrication.



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